Expand your process window with the NovaCentrix EX Series Controlled Environment Chuck. Designed for use with any PulseForge® 1200/1300/Invent™ tool, the EX Series allows sample processing beyond standard atmospheric conditions. Pre-heat samples up to 300°C or increase thermal transfer by cooling. A porous vacuum chuck minimizes thermal contact resistance and supports simple, repeatable sample placement. The EX Series sealed chamber allows purging with N₂ or any inert process gas. An external vacuum pump option is also available taking photonic curing into a vacuum environment. Take R&D to the next level with the NovaCentrix Controlled Environment Chuck EX Series.

FEATURES

- Straightforward sample processing/alignment on porous vacuum chuck surface
- User-selectable controlled temperature range from 10°C to 300°C
- Removable hinged chamber lid with quartz window allows vacuum and pressurized processes
- Vacuum to 200mT and below with external vacuum pump option
- Designed for operation on existing PulseForge 1200/1300/Invent sample tables
- Integrated bolometer holder for quick process checks

CHUCK CONFIGURATIONS

EX-1 Base Controlled Environment Chuck
- Temperature-controlled (10°- 300°) vacuum surface

EX-2 Base Controlled Environment Chuck with Sealed Chamber*
- Temperature-controlled (10°- 300°) vacuum surface
- Pressurized or vacuum processing capability (with user-supplied vacuum pump)

EX-3 Base Controlled Environment Chuck, Sealed Chamber*, and External Vacuum Pump
- Temperature-controlled (10°- 300°) vacuum surface
- Pressurized or vacuum processing (below 200 mT)

* Sealed Chamber available with two quartz window options based on expected use of the PulseForge:
  - Fused Quartz - Suitable for PulseForge operation up to 500V
  - Synthetic Fused Silica - For processing above 500V, fused silica preferred due to high UV transmittance